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Abstract Nanofabrication is playing an ever increasing role in science and technology on the nanometer scale and will soon allow us to build systems of the same complexity as found in nature. Top-down methods that emerged from microelectronics are now not only used for the fabrication of structures for integrated circuits, microelectro-mechanical systems, but also for microoptics and diverse nano-devices. In this talk, an overview of some of these methods was presented, paying particular attention to those which enable large-scale production of lithographic patterns. After reviewing the various patterning techniques, we discuss some recent application issues in the fields of microelectronics, optical elements, as well as in namo-device.

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